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(NE)

IN THE UNITED STATES PATENT & TRADEMARK OFFICE

RECEIVED
FEB 20 2003
TC 1700

IN RE APPLICATION OF :
HIROYUKI YANO ET AL : EXAMINER: DEO, D. V.
SERIAL NO: 09/531,163 :
FILED: MARCH 17, 2000 : GROUP ART UNIT: 1765
FOR: AQUEOUS DISPERSION, :
AQUEOUS DISPERSION FOR
CHEMICAL MECHANICAL
POLISHING USED FOR
MANUFACTURE OF
SEMICONDUCTOR DEVICES,
METHOD FOR MANUFACTURE OF
SEMICONDUCTOR DEVICES, AND
METHOD FOR FORMATION OF
EMBEDDED WIRING

AMENDMENT AND REQUEST FOR RECONSIDERATION

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:

Responsive to the Office Action of November 15, 2002, Applicants respectfully
request reconsideration of the above-identified application in view of the following
amendment and remarks.

IN THE CLAIMS

Please cancel Claims 44-60.

Please add the following claims:

02/14/2003 NMOHAMM1 00000033 09531163

01 FC:1201

168.00 OP